Sheet 1 of 1

FORM PTO-1449 (REV.7-80)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. 854063.523C1 APPLICANTS	APPLICATION NO. 10/621,262		
01		FORMATION DISCLOSURE Use several sheets if nec			Nicolas Demange et al. FILING DATE GROUP ART UNIT July 15, 2003 2812			
U.S. PATENT DOCUMENTS								
*EXXMINER	NE AN	CUMENT NUMBER	DATE		NAME .	CLAS	S SUBCLASS	FILING DATE IF APPROPRIATE
MA		5,350,705	09/27/94	Brassington et al.		257	295	,)
	AB	5,418,388	05/23/95	Okudaira et al.		257	295	
	AC	5,519,237 05/21/96		Itoh et al.		257	306	
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	AG	6,028,361	02/22/00	Ooishi		257	774	
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	AJ							
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OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
111	Amanuma, K. et al., "Capacitor-on-Metal/Via-stacked-Plug (CMVP) Memory Cell for							
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* EXAMINER: Initial if reference considered, whether or not criteria is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).								
conformance and not considered. Include copy of this form with next communication to applicant(s).								